

11aug05 10:53:31 User259284 Session D3256.3

SYSTEM:OS - DIALOG OneSearch

File 34:SciSearch(R) Cited Ref Sci 1990-2005/Aug W1

(c) 2005 Inst for Sci Info

File 434:SciSearch(R) Cited Ref Sci 1974-1989/Dec

(c) 1998 Inst for Sci Info

| Set | Items | Description   |
|-----|-------|---|
| S1  | 15    | CR='HARDING DR, 1994, V9, P1583, J MATER RES':CR='HARDING -<br>DR, 1995, V78, P1673, J APPL PHYS' |
| S2  | 4     | S1 NOT S1/2000-2005   |

11aug05 10:23:31 User259284 Session D3256.2

File 2:INSPEC 1969-2005/Jul W5  
 (c) 2005 Institution of Electrical Engineers

| Set | Items | Description   |
|-----|-------|---|
| S1  | 2724  | CI=(SI SS(S)N SS(S)O SS) (S)NE=3  |
| S2  | 244   | CI=(SI BIN(S)N DOP(S)O BIN) (S)NE=2   |
| S3  | 247   | CI=(SI BIN(S)N DOP(S)O BIN)   |
| S4  | 2822  | S1:S3   |
| S5  | 650   | S4 AND NI='TEMPERATURE'   |
| S6  | 147   | S5 AND TE=670:TE=900  |
| S7  | 66685 | (PECVD OR PLASMA OR PLASMAS OR CVD OR SUBSTRATE OR DEPOSIT-<br>????????) (4N)TEMP???????????    |
| S8  | 180   | 4AND7   |
| S9  | 299   | S6 OR S8  |
| S10 | 15    | S9 AND (NITROUS OR N2O)   |
| S11 | 24    | S9 AND (SILANE OR SIH4)   |
| S12 | 11    | S9 AND CI=SIH4  |
| S13 | 20    | S9 AND CI=N2O   |
| S14 | 31    | S10 OR S13  |
| S15 | 31    | S11 OR S12  |
| S16 | 17    | 14AND15   |
| S17 | 1     | S16 AND PHOTORESIST?  |
| S18 | 1     | S16 AND AMPLIFIED   |
| S19 | 1     | S16 AND (N OR NITROGEN) (4N) (CONTENT OR 01 OR 02 OR 03 OR 04<br>OR 05 OR 06 OR 07 OR 08 OR 09) |
| S20 | 0     | S16 AND (ADDITIONAL OR EXTRA OR FINAL)  |
| S21 | 0     | S16 AND "STEP"  |
| S22 | 0     | S16 AND "STEPS"   |
| S23 | 2     | S17:S19   |
| S24 | 0     | S7 AND S6 AND S16   |
| S25 | 3     | S7 AND S6 AND S10:S16   |
| S26 | 3     | S25 NOT S23   |
| S27 | 242   | (NITROUS OR N2O OR CI=N2O) AND (SILANE OR SIH4 OR CI=SIH4)                                      |
| S28 | 56    | S4 AND S27  |
| S29 | 2     | 6AND28  |
| S30 | 15    | 7AND28  |
| S31 | 15    | S29:S30 NOT (S23 OR S26)  |
| S32 | 15    | S31 AND S1:S9   |
| S33 | 15    | S32 AND (TEMPERATURE? ? OR NI=TEMP?)  |
| S34 | 3     | S33 AND ETCH?????????   |
| S35 | 0     | S33 AND EXPOS?????????  |
| S36 | 1     | S33 AND (OXIDAT? OR OXIDI? OR NITRIDED OR NITRIDI? OR NITR-<br>IDA? OR NITROGENA?)              |
| S37 | 4     | S34:S36   |
| S38 | 2     | 6AND33  |

FILE 'REGISTRY' ENTERED AT 09:02:55 ON 11 AUG 2005

L1 21705 S O.SI/MF OR O SI/ELF  
L2 429 S N.O.SI/MF OR N O SI/ELF

FILE 'STNGUIDE' ENTERED AT 09:03:13 ON 11 AUG 2005

FILE 'REGISTRY' ENTERED AT 09:32:20 ON 11 AUG 2005

L3 40 S N/MF  
L4 27 S O2/MF  
L5 28 S N2 O/MF

FILE 'USPATFULL' ENTERED AT 09:36:32 ON 11 AUG 2005

E 257629/NCL  
L6 1137 S (257629000/NCL OR 257630000/NCL OR  
257631000/NCL OR 257632000/NCL OR 257633000/NCL OR 257634000/NCL  
OR 257635000/NCL OR 257636000/NCL OR 257637000/NCL OR  
257638000/NCL OR 257639000/NCL OR 257640000/NCL OR 257641000/NCL  
OR 257642000/NCL OR 257643000/NCL OR 257644000/NCL OR  
257645000/NCL OR 257646000/NCL OR 257647000/NCL OR 257648000/NCL  
OR 257649000/NCL OR 257650000/NCL OR 257651000/NCL) AND  
(METHOD OR FABRICATION OR MAKING OR PROCESS OR FORMING OR  
FORMATION)/TI  
L7 310 S L6 AND (SILICA OR SIO OR SIO2 OR SION OR  
(SI OR SILICON) (S) (OXIDE OR DIOXIDE OR OXYNITRIDE)) /TI,AB  
L8 109 S L7 AND FILM/TI,AB  
L9 19 S L8 AND TEMPERATURE/TI,AB  
L10 3 S L9 AND PLASMA/TI,AB  
D TI 1-3  
L11 29 S L6 AND (SILICA OR SIO OR SIO2 OR SION OR  
(SI OR SILICON) (S) (OXIDE OR DIOXIDE OR OXYNITRIDE)) /TI  
L12 32 S (L10 OR L11)  
L13 SEL PLU=ON L12 1- NCL IC : 234 TERMS

FILE 'CAPLUS' ENTERED AT 09:40:47 ON 11 AUG 2005

L14 116067 S L13  
L15 30619 S L14 AND (L1 OR L2 OR L3 OR L4 OR L5)

FILE 'STNGUIDE' ENTERED AT 09:41:08 ON 11 AUG 2005

FILE 'CAPLUS' ENTERED AT 09:41:48 ON 11 AUG 2005

L16 128139 S (SILICA OR SIO OR SIO2 OR SION OR (SI OR  
SILICON) (W) (OXIDE OR DIOXIDE OR OXYNITRIDE)) (4A) (FILM OR  
?LAYER? OR ?COAT? OR DEPOSIT?)  
L17 15310 S L14 AND L16  
L18 13120 S L15 AND L16  
L19 18280 S (L1 OR L2) AND (L3 OR L4 OR L5)  
L20 5979 S L16 AND L19  
L21 1723 S (L17 OR L18) AND L19  
L22 5979 S (L20 OR L21)  
L23 4400 S L22 AND (PROCESS OR METHOD OR "STEP" OR  
"STEPS")  
L24 1730 S L22 AND (TEMPERATURE OR 400 OR 410 OR 420  
OR 430 OR 44 OR 450 OR 460 OR 470 OR 480 OR 490 500)  
L25 1306 S L16 AND L23 AND L24  
L26 7 S L25 AND L3(L)MOA/RL

L27 31 S L25 AND L2  
 L28 29 S L27 NOT L26  
 L29 21 S L28 NOT P/DT  
 L30 13 S L29 AND PY>1999  
 L31 8 S L28 NOT L29  
 L32 4 S L31 AND PRY>1999  
 L33 3 S L31 AND (1999 OR 1998 OR 1997 OR 1996)/PY,P  
 RY  
 L34 12 S L28 NOT (L30 OR L32)  
 L35 16 S L31 OR L33 OR L34  
 L36 16 S L35 NOT L26  
 D ALL HITSTR TOT  
 L37 19566 S (L17 OR L18 OR L19 OR L20 OR L21 OR L22 OR  
 L23 OR L24 OR L25) AND L16  
 L38 6407 S L37 AND (TEMPERATURE OR C OR DEGC OR DEG  
 OR DEGREE OR CELSIUS OR 400 OR 450 OR 500 OR 670 OR 675 OR 680  
 OR 685 OR 690 OR 695 OR 700 OR KELVIN)  
 L39 34909 S (EXPOS##### OR PLASMA) (4A) (N2 OR NITROGEN  
 OR N2O OR NITROUS OR OXIDA? OR OXIDI? OR OXIDED OR NITROGENA?  
 OR NITRIDED OR NITRIDI? OR NITRIDA?)  
 L40 7851 S (EXPOS##### (4A) PLASMA)  
 L41 368 S L38 AND (L39 OR L40)  
 L42 213080 S (N OR NITROGEN) (4A) (WT OR WEIGHT OR CENT  
 OR PERCENT? OR CONCENTRATION OR CONC OR CONCN OR LEVEL OR IONS  
 OR ATOMIC OR ATOMS OR AMOUNT OR DENSITY)  
 L43 30 S L41 AND L42  
 L44 172 S L38 AND L42  
  
 FILE 'REGISTRY' ENTERED AT 10:00:43 ON 11 AUG 2005  
 L45 34 S H4 SI/MF  
  
 FILE 'CAPLUS' ENTERED AT 10:01:48 ON 11 AUG 2005  
 L46 137 S (L41 OR (L43 OR L44)) AND (L45 OR SIH4 OR  
 SILANE)  
  
 FILE 'CAPLUS' ENTERED AT 10:02:09 ON 11 AUG 2005  
 L47 166 S (L41 OR (L43 OR L44)) AND (L5 OR NITROUS  
 OR N2O)  
 L48 98 S L46 AND L47  
 L49 94 S L48 NOT (L36 OR L26)  
 L50 94 S L49 AND L16  
 L51 15 S L50 AND L42  
 L52 0 S L50 AND CHEMICALLY AMPLIFIED  
 L53 1 S L50 AND (RESIST(4A) (PHOTO##### OR  
 LIGHT##### OR RADIAT##### OR IRRADIAT#####) OR PHOTORESIST  
 )  
 L54 15 S (L51 OR L52 OR L53)  
 D ALL HITSTR TOT  
 L55 40422 S (01 OR 08 OR 09 OR 02 OR 03 OR 04 OR 05 OR  
 06 OR 07) (2A) (ATOMIC OR N OR NITROGEN)  
 L56 202 S L16 AND L55  
 L57 3 S L56 AND (L5 OR NITROUS)  
 L58 23 S L56 AND (L45 OR SIH4 OR SILANE)  
 L59 3 S L57 AND L58  
 L60 3 S L59 NOT (L54 OR L35 OR L26)  
 D ALL HITSTR TOT

09/597,161

L61 70933 S ADD#####(4A) (N OR NITROGEN) OR NITROGENAT  
#####  
L62 7 S ((L47 OR L48 OR L49 OR L50) OR L56 OR L58)  
AND L61  
L63 6 S L62 NOT (L59 OR L54 OR L35 OR L26)  
D ALL HITSTR TOT  
L64 531 S (L43 OR L44) OR (L46 OR L47 OR L48 OR L49  
OR L50 OR L51 OR L52 OR L53 OR L54) OR (L56 OR L57 OR L58 OR  
L59 OR L60) OR (L62 OR L63)  
L65 79 S L64 AND (L2 OR L3 OR L61 OR SION)  
L66 SEL PLU=ON L65 1- PRN : 46 TERMS

FILE 'WPIX, JAPIO' ENTERED AT 10:13:20 ON 11 AUG 2005

L67 54 S L66  
L68 35 S L67 AND (N2 OR N OR N2O OR NITROUS OR  
NITROGEN? OR NITRIDED OR NITRIDAT? OR NITRID?)  
L69 6 S L68 AND (SILANE OR SIH4)  
D MAX 1-6  
L70 0 S ADD#####(4A) (N OR NITROGEN) AND L67  
L71 2 S L67 AND (N OR N2 OR N2O OR NITROUS OR  
NITROGEN? OR NITRID? OR SION)/TI  
L72 2 S L71 NOT L69  
D MAX 1-2  
L73 9 S L67 AND OXYNITRID?  
L74 7 S L73 NOT (L71 OR L69)